

On Pioneering Nanometer-Era Routing Problems

An Appreciation of Professor CL Liu's visionary approach to Physical Design

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Introduction

- A true anecdote...
 - At an early 90s conference, a presenter told the story of searching under a lamppost
 - Joke about theoretician stereotypes
 - Prof. Liu stood up to defend theoreticians
- Motto: search for interesting problems and solutions, pique interest and fellowship
- Numerous contributions by Prof. Liu
 - Transforming EDA from *ad hoc* heuristics to algorithmic research
 - Pioneered works in logic synthesis, floorplanning, placement, routing, …
 - Predicting future EDA challenges, and stimulating innovative research
 - Illustrated in this presentation with examples in modern routing area





Importance of Predicting the Future

- Complex EDA problems take years to converge
 - Industry moves to a new node quickly
 - Solutions are needed shortly after difficulties first encountered
 - Example: mad scramble for 20nm DPT
 - Fill the gap between academia and industry
 - Industry is pre-occupied with tactical revenue driven issues
 - Academia and research institutes are best suited to research into future difficult problems





Challenges and Rewards of Researching into the Future

- Challenges
 - Requires strong vision and intuition to predict the future
 - Takes instinct, and years of experience and observation
 - With Prof. Liu, it is a consistent trait
 - For example, his real time scheduling work
 - Requires strong leadership and drive to initiate research into new areas
 - Requires keen sense of judgment along the way and flexibility to adjust
 - Flexibility to adjust: my first topic (optical switch routing) dropped in half a year
 - Continued focus when on the right track: years of research into Channel Routing
- Rewards
 - Accredited as pioneers of new areas
 - Exert leadership and gain fellowships
 - Easier to publish papers great news for students[©]
 - Not the easy way out though others need to agree with the topics' relevance

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Prof. Liu's Early Works in Routing

- Early works focused on Channel routing problems
 - Influential early work done by Prof. Kuh's group
 - "Efficient algorithms for channel routing", TCAD'82, T Yoshimura and ES Kuh
 - Prof. Liu's group was one of the most active research groups in early 80s
 - "A new channel routing problem", DAC'83, HW Leong and CL Liu
 - "Permutation channel routing", ICCD'85, HW Leong and CL Liu
 - "Simulated annealing channel routing", ICCAD'85, HW Leong, DF Wong, and CL Liu
 - "Compact channel routing with via placement restriction", VLSI'86, DF Wong and CL Liu

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- Extended to multi-layer channel and over the cell routing
 - "A new approach to three- or four-layer channel routing", TCAD'88, J Cong, DF Wong, and CL Liu
 - "Over the cell channel routing", ICCAD'88, J Cong and CL Liu
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- Extended to FPGA architecture
 - "A channel router for single layer customization technology", ICCAD'91, Y Sun, SK Dong, S Sato, and CL Liu
 - "Two channel routing algorithms for quickly customized logic", EDAC'93, SK Dong, Y Sun, S Sato, and CL Liu

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Routing Problems in 80s and early 90s

- Router's role: maximize route completion with minimal wirelength
 - Little attention to performance
 - Delay dominated by cells little attention to wire RC
 - Homogenous metal stacks with few routing layers little need for timingdriven layer assignment
 - Feature sizes much larger than litho wave length
 - Few, simple design rules
 - Most routing related research was in topology generation
- Routing was mostly an industry chip-finishing step
 - Relatively few research activities



Routing Technology Industry Trend

- Semi industry: new process node every 2 years
 - Devices become faster, while interconnect wires become thinner with closer proximity
 - circuit performance: more dominated by interconnect Rs and Cs
 - Significant crosstalk impact on circuit performance
 - Layer stacks become very heterogeneous
 - RC varies as much as 50x between layers,
 - Significant timing variation due to layer assignment
- Design sizes explode with emphasis on low power
 - Wires travel over longer distances
 - Weaker drivers
- Interconnect optimization is becoming the center-stage of physical design





Bohr, "Intel's 65 nm Logic Technology", Aug. 2004



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Routing Technology Industry Trend Process aspect

- Semi industry: new process node every two years
 - Litho technology cannot keep up with shrinking feature sizes
 - Major jump in complicated design rules
 - Need for other innovations such as redundant via insertion and double/triple patterning (DPT/TPT)





Predicting the Future

- Vision is always 20/20 in retrospective
 - Difficult to see today's routing trends in 80s & 90s
 - It would be too late to start on today's problems now
- Crucial to start EDA research before a process is ready
- Prof. Liu's crystal ball...
 - Asked me to work on crosstalk driven routing in 1992
 - "Minimum crosstalk channel routing", T Gao and CL Liu, 1993
 - "Minimum crosstalk switchbox routing", T Gao and CL Liu, 1994
 - Today
 - Over the next decade, spurred much academic research with many publications
 - One of the most emphasized areas in timing optimization in industry today



Crosstalk Driven Detailed Routing

- Crosstalk driven routing: an unique marriage between an important future problem with an algorithmic approach
 - Channel routing is a track assignment problem with vertical constraints
 - Crosstalk can be roughly modeled with parallel wires on adjacent tracks
 - Mixed integer linear programming solver advanced significantly in 90s
 - Crosstalk driven channel/switchbox routing problems was formulated as mixed integer linear programming problem
 - Optimize track/layer permutation to optimize for crosstalk and wire length
- Impact on EDA industry
 - The exact formulation is not used now as industry moved to area routing
 - Set an algorithmic direction to solve crosstalk problem during routing
 - Brought great awareness of crosstalk and spurred much research
 - Many papers published.
 - Laid foundation to today's crosstalk driven routing solutions
 - Industry routers today still control wire spacing and layers for crosstalk control



Predicting the Future (cont.)

- Prof. Liu's crystal ball...
 - Advised Prashant to work on timing-driven layer assignment in 1997
 - "A performance-driven layer assignment algorithm for multiple interconnect trees", P Saxena and CL Liu, 1998
 - Today
 - Layer stacks can be very heterogeneous, with many routing layers and RC variations among layers as much as 50x
 - Layer assignment can dominate wire delay
 - Timing-driven layer assignment is crucial to design closure



Bohr, "Intel's 65 nm Logic Technology", Aug. 2004



Performance Driven Layer Assignment

- The challenge was to balance routability against net criticality during layer assignment
 - Addressed timing-driven layer assignment in the context of congestionrelated tradeoffs inside a router
 - Introduced a dynamically adjusted "quota" for each net to ameliorate net ordering problem
 - Prevents early-routed nets from monopolizing the "good" layers
 - Used congestion-aware "lookahead key" to evaluate delay impact of moving to next layer
- Impact on EDA industry
 - The notion of "historical congestion" of a gcell implicit in dynamic quotas is the basis of "negotiated" routing in modern routers
 - Layer assignment has increasing effects on timing convergence in increasing number of designs
 - Router needs to be layer RC aware
 - Physical synthesis needs to model the layer assignment





Routing Technology Industry Trend Process aspect

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The DNA Lives On

Continuing Prof. Liu's Tradition...

Antenna effect

- L.-D. *Huang, X.* Tang, H. Xiang, D. F. Wong, and I.-M. Liu, "A polynomial time optimal diode insertion/routing algorithm for fixing antenna problem", DATE, 2002. (TCAD)
 - Seminal work on routing with diode insertion
- T.-Y. Ho, Y.-W. Chang, and S.-J. Chen, "Multilevel routing with antenna avoidance," *ISPD*, 2004.
- B.-Y. Su and Y.-W. Chang, ``An optimal jumper insertion algorithm for antenna effect avoidance/fixing ," DAC, 2005 (TCAD, 2006)
- B.-Y. Su, Y.-W. Chang, and J. Hu, ``An optimal jumper insertion algorithm for antenna effect avoidance/fixing on general routing trees with obstacles," *ISPD*, 2006 (TCAD, 2007)
- J. Wang and H. Zhou "Optimal jumper insertion for antenna avoidance under ratio upper-bound", DAC, 2006 (TCAD, 2007)
- Z.-W. Jiang and Y.-W. Chang, "An optimal simultaneous diode/jumper insertion algorithm for antenna fixing," ICCAD, 2006. (TCAD, 2008)

Redundant Via Insertion

- G. Xu, L. Huang, D. Z. Pan and M. D.-F. Wong, "Redundant-via enhanced maze routing for yield improvement". *ASP-DAC*, 2005.
- K.-Y. Lee and T.-C. Wang, "Post-routing redundant via insertion for yield/reliability improvement," ASP-DAC, 2006 (Best Paper Award)
- H.-Y. Chen, M.-F. Chiang, Y.-W. Chang, L. Chen, and B. Han, "Novel full-chip gridless routing considering double-via insertion," *DAC*, 2006.
- K.-Y. Lee, T.-C. Wang and K.-Y. Chao, "Post-routing redundant via insertion and line end extension with via density consideration," ICCAD, 2006
- K.-Y. Lee, C.-K. Koh, T.-C. Wang, and K.-Y. Chao, "Optimal post-routing redundant via insertion," *ISPD*, April 2008 (Best Paper Nominee)
- K.-Y. Lee, S.-T. Lee, and T.-C. Wang, "Redundant via insertion with wire bending," *ISPD*, 2009
- S.-T. Lin, K.-Y. Lee, T.-C. Wang, C.-K. Koh, and K.-Y. Chao, "Simultaneous redundant via insertion and line end extension," ASP-DAC, 2011.



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OPC routing

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- Y.-R. Wu, M.-C. Tsai, and T.-C. Wang, "Maze routing with OPC consideration," *ASP-DAC*, 2005.
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- P. Yu and D. Z. Pan, "TIP-OPC: A New topological invariant paradigm for pixel based optical proximity correction". *ICCAD*, 2007
- P. Yu and D. Z. Pan, "A Novel Intensity Based OPC Algorithm with Speedup in Lithography Simulation". ICCAD, 2007
- T.-C. Chen, G.-W. Liao, and Y.-W. Chang, "Predictive formulae for OPC with applications to lithography-friendly routing," DAC, 2008 (TCAD 2010, Best paper nominee)
- M Cho, K Yuan, Y Ban, and D. Pan, "ELIAD: Efficient lithography aware detailed router with compact post-OPC printability prediction," DAC 2008. (TCAD 2009)
- S.-L. Huang, C.-W. Lin, and Y.-W. Chang, "Provably good OPC modeling and its applications to interconnect optimization," ICCD, 2010 (Best paper award).
- Y.-H. Lin, Y.-C. Ban, D. Z. Pan and Y.-L. Li, "DOPPLER: DPL-aware and OPC-friendly gridless detailed routing with mask density balancing", ICCAD, 2011
- Y. Du, H. Zhang, M. Wong, K. Chao, "Hybrid Lithography Optimization with E-Beam and ArF Immersion Process for 16nm 1D Gridded Design", ASPDAC 2012

CMP routing

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- K. S.-M. Li, C.-L. Lee, Y.-W. Chang, C.-C. Su, and J. E Chen, "Multilevel full-chip routing with testability and yield enhancement," *TCAD*, September 2007.
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- W. Jang, O. He, J.-S. Yang and D. Z. Pan, "Chemical-Mechanical Polishing Aware Application-Specific 3D NoC Design", ICCAD, 2011



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Double patterning

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- K. Yuan, J. Yang and D. Z. Pan, "Double Patterning Layout Decomposition for Simultaneous Conflict and Stitch Minimization", *ISPD*, 2009 (TCAD)
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- J.-R. Gao and D. Z. Pan, "Flexible Self-aligned Double Patterning Aware Detailed Routing with Prescribed Layout Planning", *ISPD*, 2012
- Z. Xiao, Y, Du, H. Zhang, M. Wong, "A Polynomial Time Exact Algorithm for Self-Aligned Double Patterning Layout Decomposition", ISPD, 2012.

Triple patterning

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- Q. Ma, H. Zhang, M. Wong, "Triple Patterning Aware Routing and Its Comparison with Double Patterning Aware Routing in 14nm Technology", DAC 2012.
- S.-Y. Fang and Y.-W. Chang, "A novel layout decomposition algorithm for triple patterning lithography," *DAC*, 2012.



The DNA Lives On Continuing Prof. Liu's Tradition...

- E-beam
 - K. Yuan and D. Z. Pan, "E-beam lithography stencil planning and optimization with overlapped characters", *ISPD*, 2011 (Best Paper Award)
 - S.-Y. Fang and Y.-W. Chang, "Graph-based subfield scheduling for electron-beam photomask fabrication," *ISPD*, 2012
- EUV
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 - S.-Y. Fang and Y.-W. Chang, "Simultaneous flare level and flare variation minimization with dummification in EUVL," DAC, 2012.



Current and Upcoming Challenges

- Process challenges mismatch between feature sizes and litho technology continues
 - Growing complex design rules hurt run time and QoR
 - Is there a more scalable approach?
 - Design-rule compilers?
 - Restrictive patterns?
 - What is next after LELE DPT and possible solutions?
- Timing challenges interconnect delay impact needs to be modeled and optimized throughout physical synthesis
 - Pre-route optimization
 - How to better model routing interconnect?
 - How to ensure correlation without over-constraining routing?
 - Post-route optimization
 - Needs stronger better integrated ECO flow between routing and optimization

Thank You Prof. Liu!!!

- For help in transforming EDA from ad hoc heuristics to algorithmic research
- For foreseeing future challenges, and pioneering and leading researches into them
- For being the best advisor possible

